



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 9635**
Satoshi MAEMORI et al. : Docket No. 2001_1300A
Serial No. 09/955,111 : Group Art Unit 1752
Filed September 19, 2001 : Examiner Sin Lee

POSITIVE-WORKING PHOTORESIST
COMPOSITION AND PHOTSENSITIVE
MATERIAL USING SAME

RESPONSE TO FINAL REJECTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Final Rejection dated September 5, 2003, the period for response having been extended by the filing of the accompanying RCE and Petition for Three Month Extension of Time, please amend the present application as follows:

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TC 1700